

## PATENT ABSTRACTS OF JAPAN

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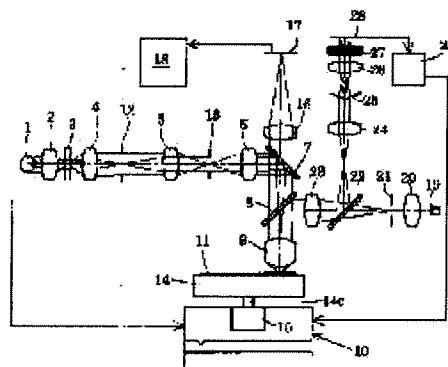
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## (54) APPARATUS FOR INSPECTING SUPERPOSITION

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide an apparatus for inspecting superposition that accurately inspects the mount of slippage of superposition by properly correcting the influence of distortion aberrations of an optical system.

SOLUTION: The device for inspecting overlap, measuring the slippage amount of overlap of first and second marks, is provided with lighting systems (1-9) for illuminating a overlap mark composed of the first and second marks formed on the surface (11) of an object, imaging optics (9, 16) for forming an image of the overlap mark on an image surface, and detecting systems (17 and 18) for detecting the image of the overlap mark formed on the image surface. Based on distortion aberrations of the imaging optics and decentering of an optical axis, the positions of feature points of the first and second marks are compensated according to a coordinate within the image surface, and the slippage amount of overlap is found, based on the position of the compensated feature point.



## LEGAL STATUS

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